## Study of the niobium oxide structure and microscopic effect of plasma processing on the Nb surface



Background

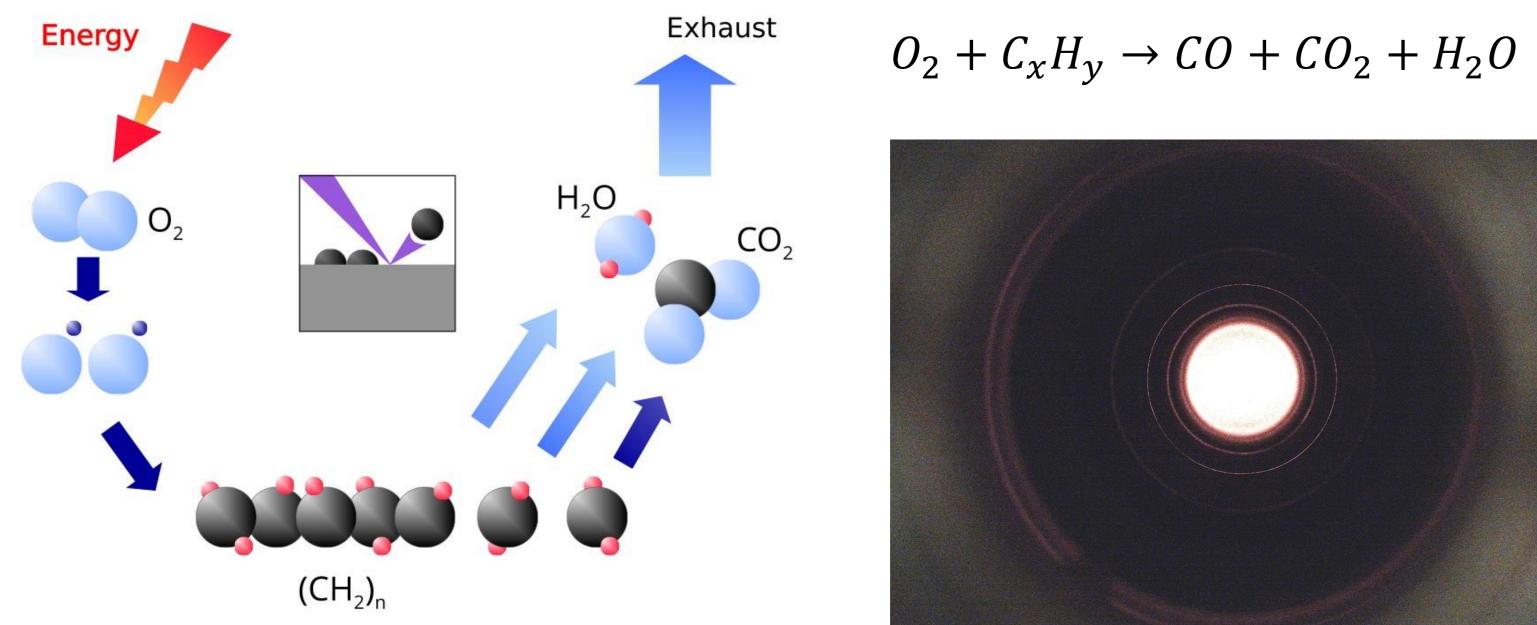
B. Giaccone<sup>1,2</sup>, M. Martinello<sup>1</sup>, J.F. Zasadzinski<sup>2</sup> FNAL, Batavia, IL 60510, USA - <sup>2</sup> IIT, Chicago, IL 60616, USA

### 1. Abstract

A study of the niobium oxide structure is presented here, focusing on the niobium suboxides. Multiple steps of argon sputtering and XPS measurements were carried out until the metal surface was exposed. Subsequently, the sample was exposed to air for different time intervals and the oxide regrowth was studied. In addition, three Nb samples prepared with different surface treatments were studied before and after being subjected to plasma processing. The scope is investigating the microscopic effect that the reactive oxygen contained in the glow discharge may have on the niobium surface. This study suggests that the Nb<sub>2</sub>O<sub>5</sub> thickness may increase. Nevertheless, since the Nb<sub>2</sub>O<sub>5</sub> is dielectric, its thickening would not negatively affect the cavity performance.

## 2. Plasma processing to mitigate FE

- Reducing FE through  $C_x H_v$  removal from cavity Nb surface
- Increasing the niobium work function by 10% results in 15% increase in E<sub>acc</sub>



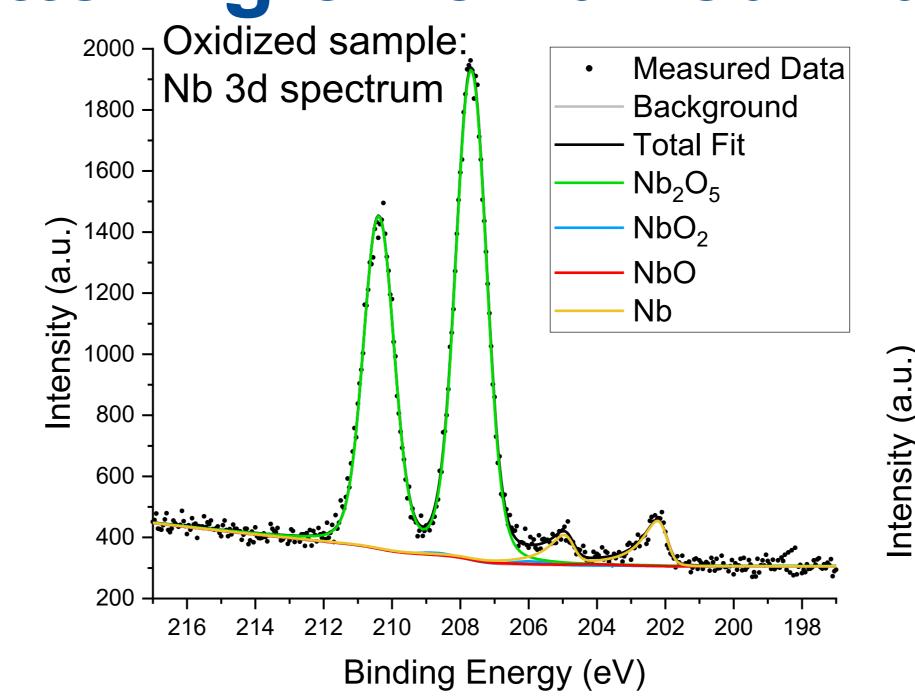


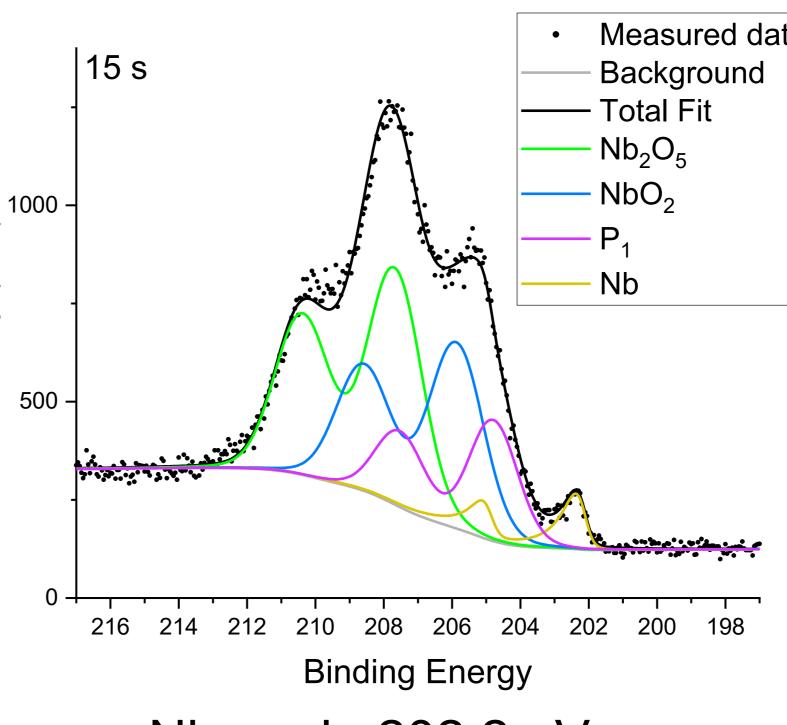
M. Doleans *et al*, NIMA 812 (2016)

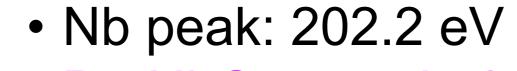
P. Berrutti, B. Giaccone *et al.*, J. Appl. Phys. 126, 023302 (2019) B. Giaccone et al., Phys. Rev. Accel. Beams 24, 022002

## 3. Argon ions sputtering on oxidized Nb sample

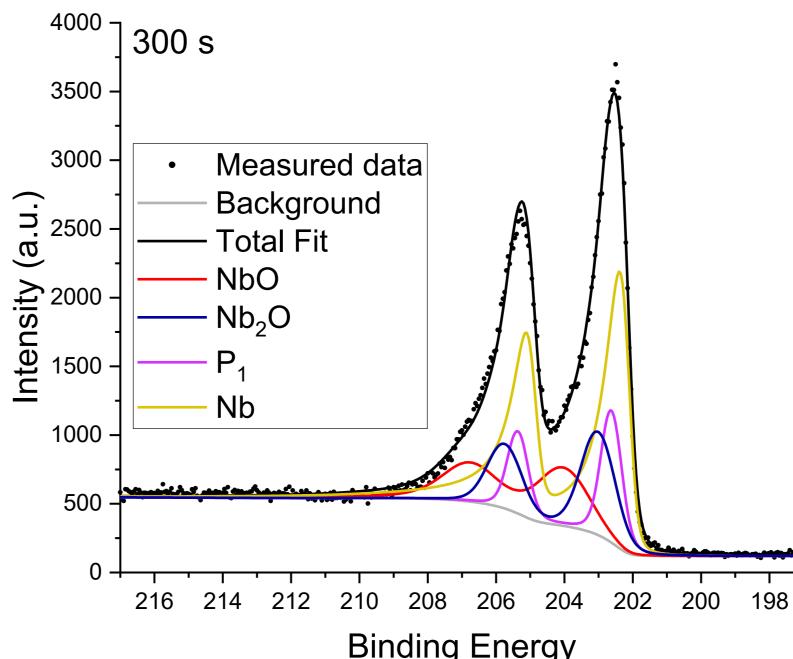
- Sample preparation: 800 °C x 3h + 20 µm EP + 5 min HF rinse
- After surface treatment: 1 week to fully oxidize prior to XPS measurement

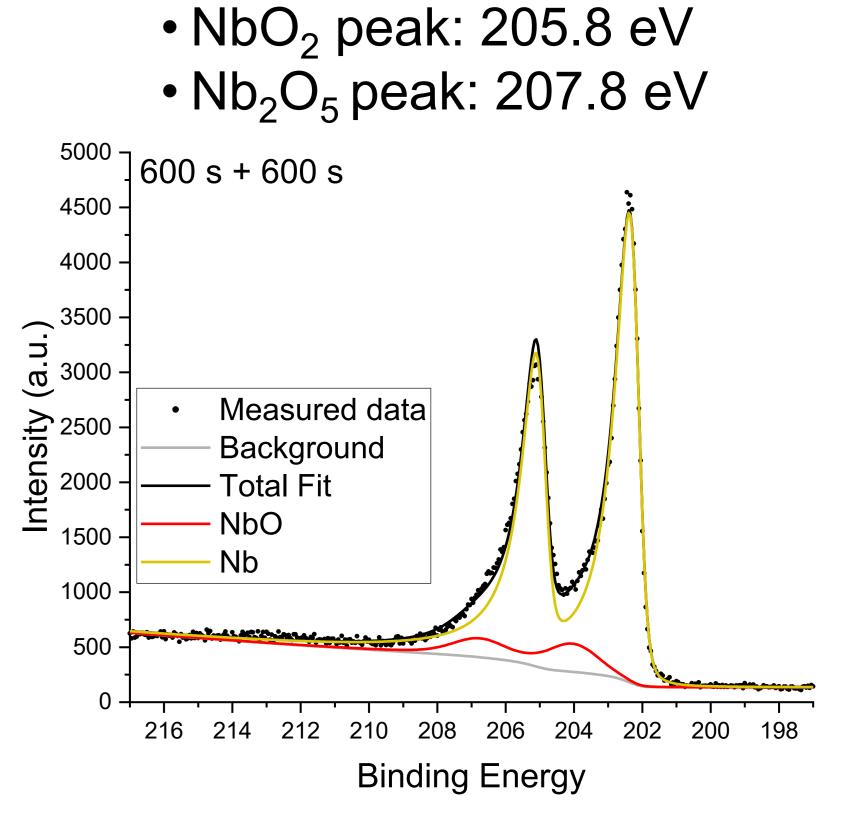






- P<sub>1</sub>: NbO<sub>1+x</sub> peak: 204.8 eV
- NbO<sub>2</sub> peak: 205.9 eV
- Nb<sub>2</sub>O<sub>5</sub> peak: 207.7 eV





Binding Energy

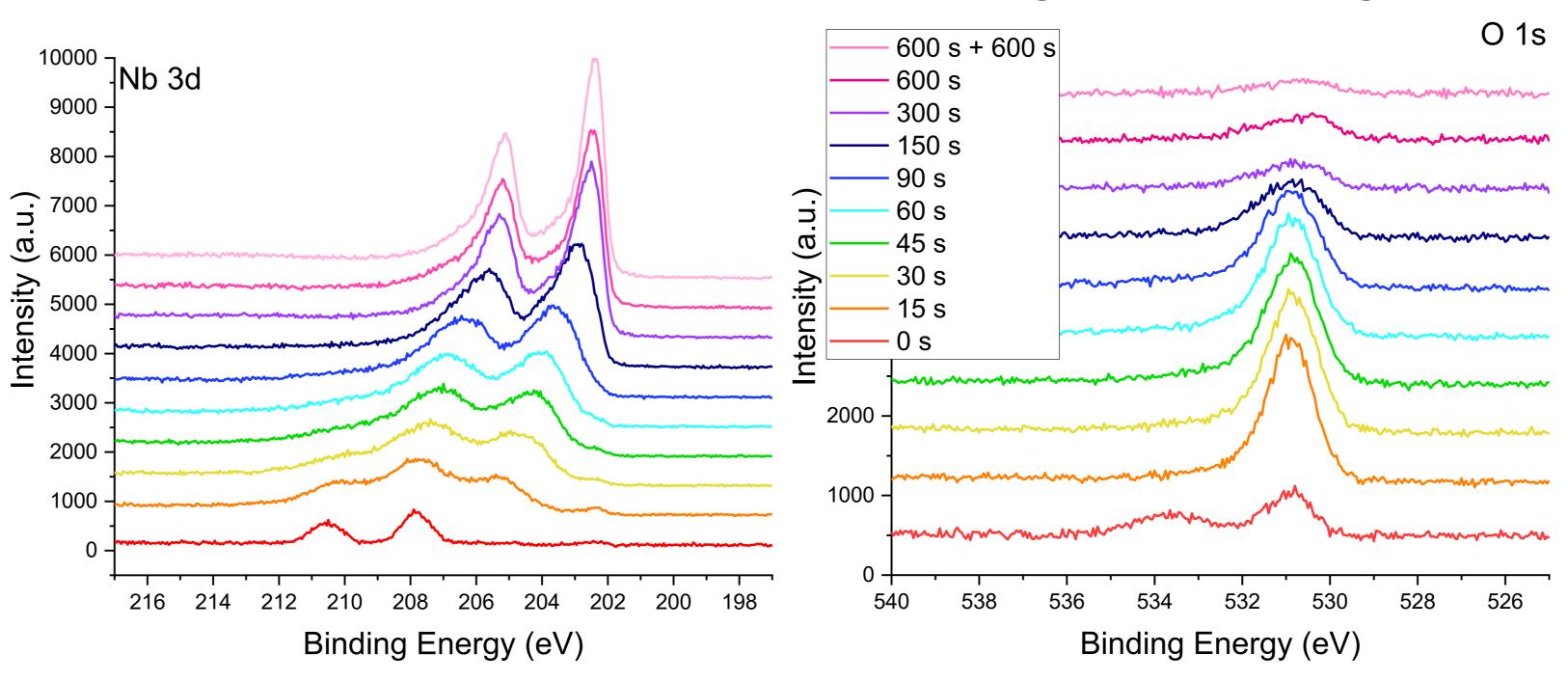
Nb peak: 202.2 eV

NbO peak: 203.8 eV

- Nb peak: 202.2 eV
- P<sub>1</sub>: Nb<sub>2+x</sub>O: 202.6 eV
- Nb<sub>2</sub>O peak: 203 eV
- NbO peak: 203.8 eV
- Nb peak: 202.2 eV NbO peak: 203.8 eV
- P<sub>1</sub> here identifies a nonstoichiometric oxide peak whose energy decreases at each sputtering step as its chemical state is modified by the Ar ions.

Nb 3d core level spectra

 After 600 s of sputtering: sample kept under vacuum for 12 h, followed by additional 600 s of sputtering and final measurement prior to oxide regrowth in air.

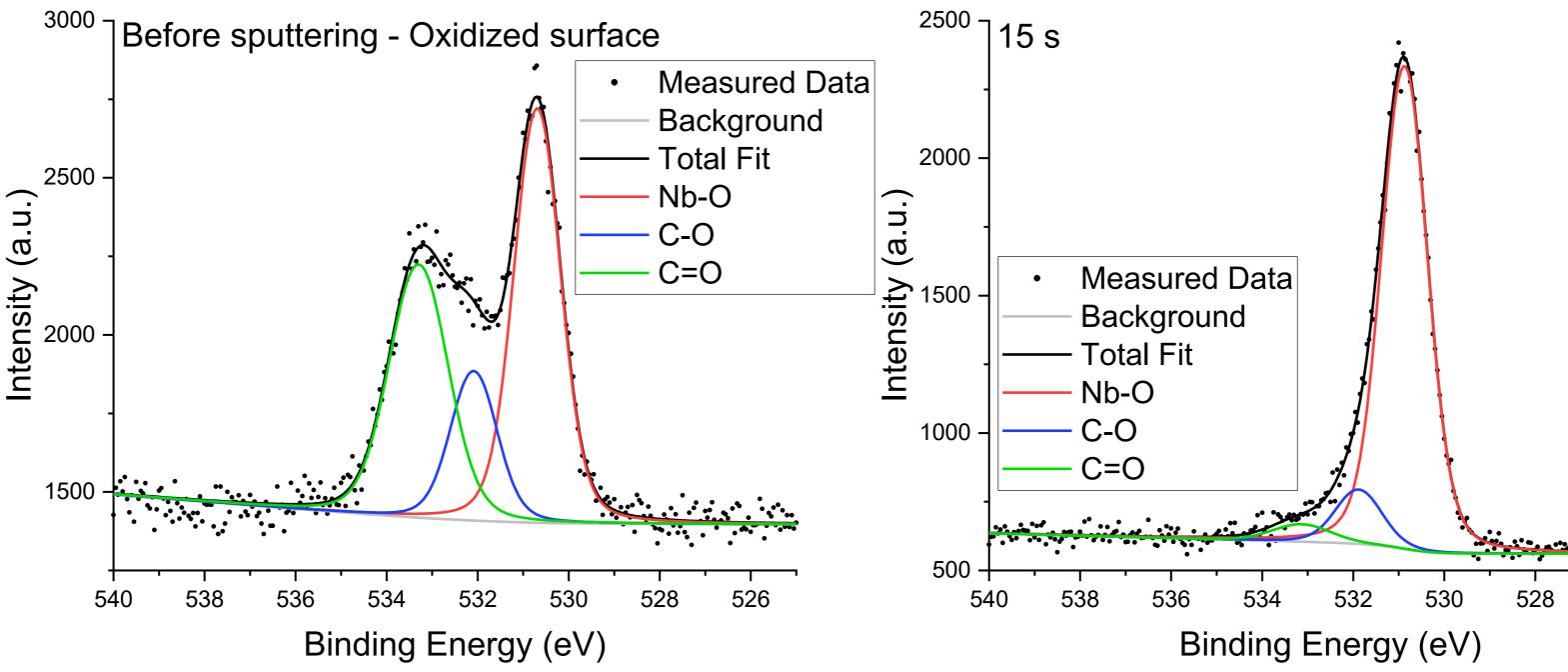


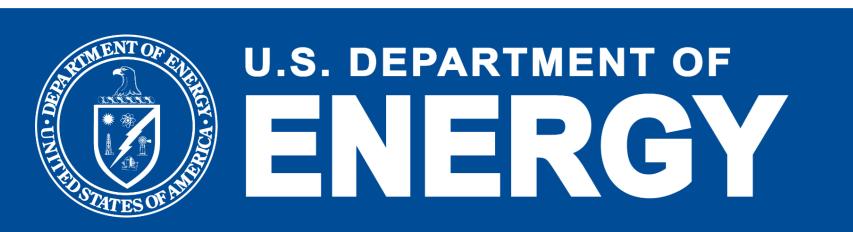
Spectra acquired during sputtering



 O 1s: initially three peaks are detected: niobium oxide, C-O, C=O. The niobium oxide peak is due to Nb<sub>2</sub>O<sub>5</sub> plus the suboxides

#### O1s core level spectra









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## 4. Oxide growth through air exposure

Air exposure steps

 $15 \min \text{ in air} + 30 \min \text{ AP}^*$ 

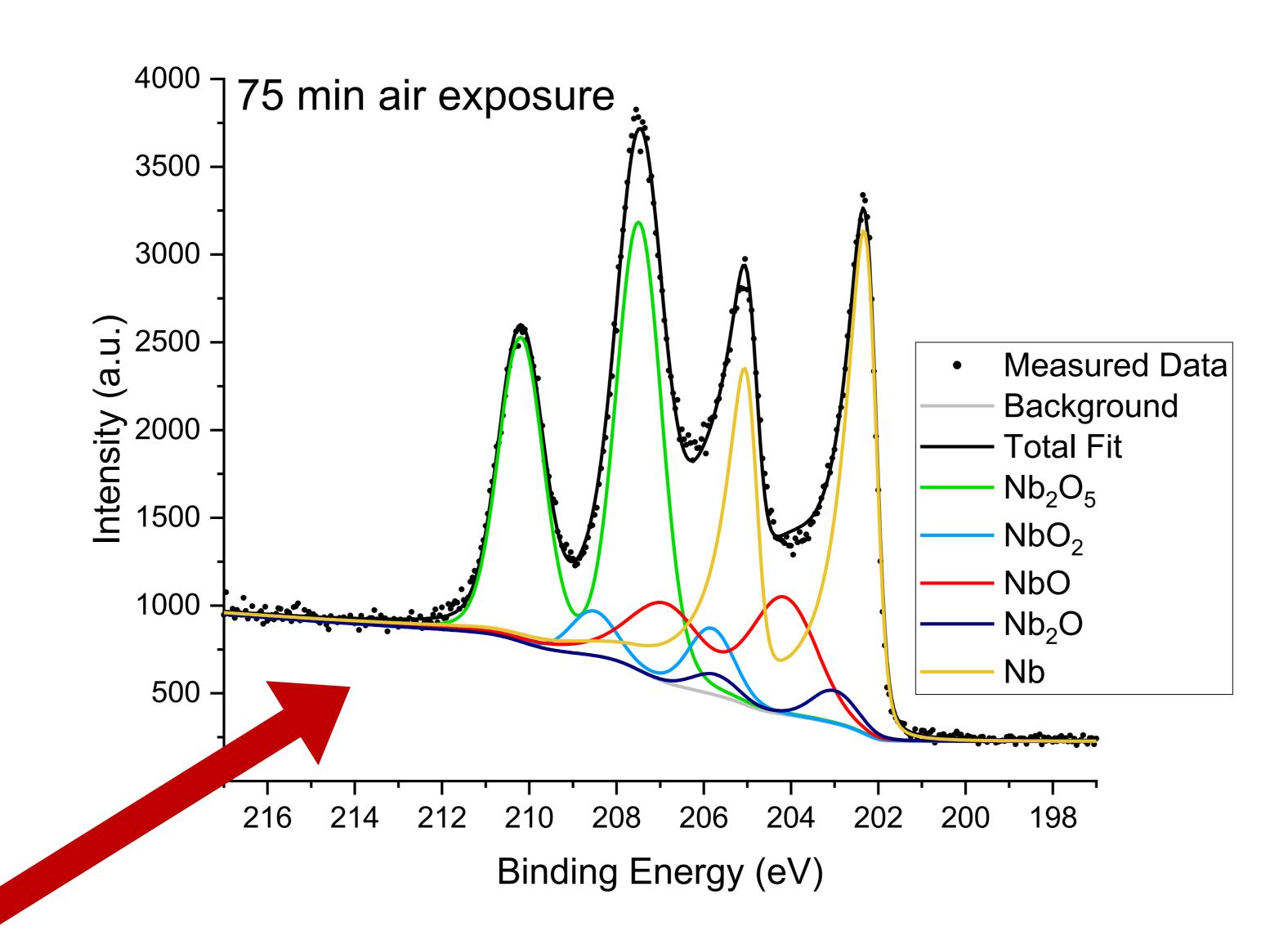
Additional (15 min in air + 30 min AP)

Total of  $(30 \,\text{min in air} + 60 \,\text{min AP}) + \text{additional } 38 \,\text{h} \text{ in vacuum}$ Additional  $(45 \,\text{min in air} + 30 \,\text{min AP}) + 38 \,\text{h} \text{ in vacuum}$ 

After 75 minutes of exposure to air: surface has not reached full oxidization.

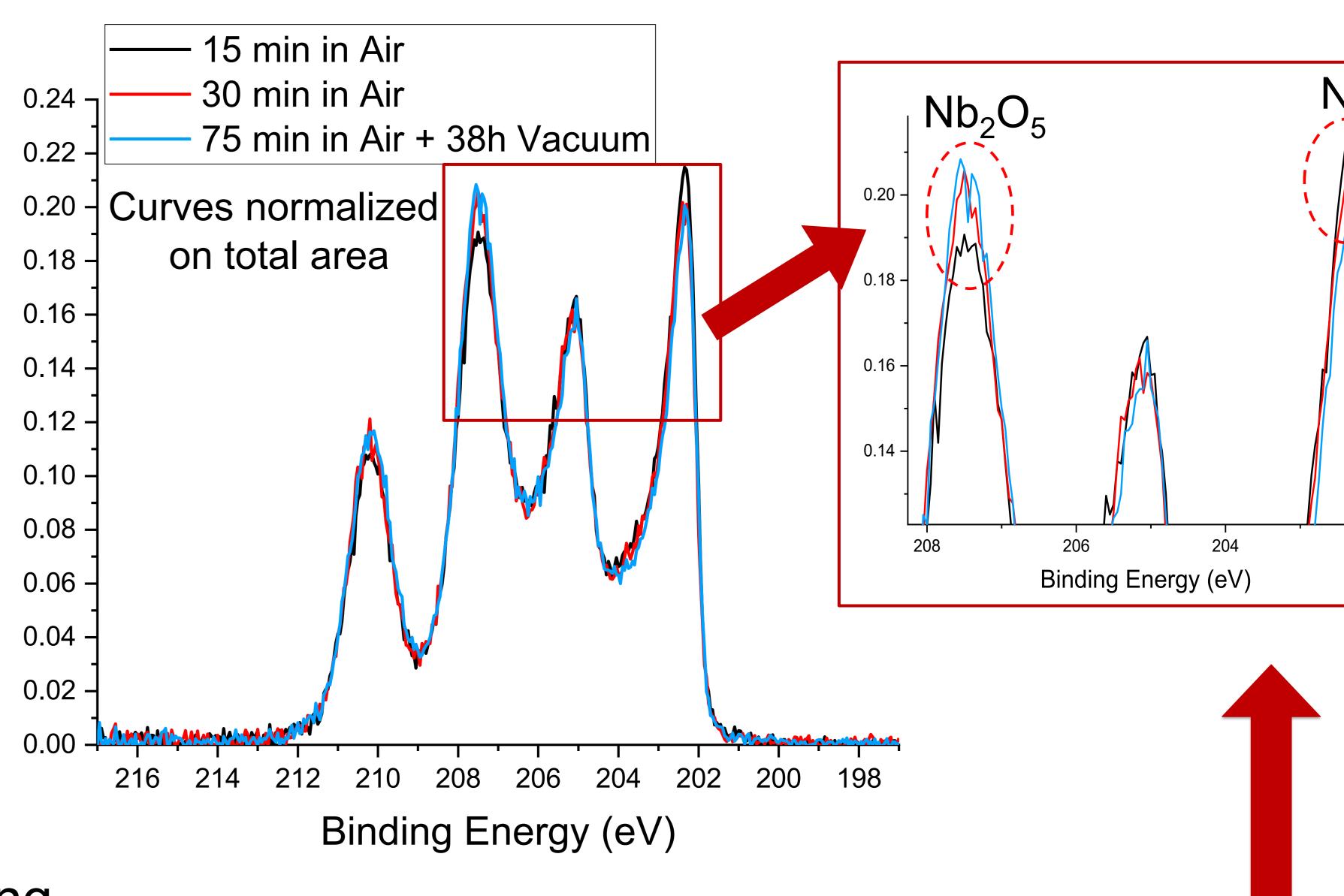
Multiple suboxides were identified through curve fitting: NbO, NbO<sub>2</sub>, Nb<sub>2</sub>O

The initial measurements taken on the oxidized sample showed possible traces of NbO and NbO<sub>2</sub>, but no Nb<sub>2</sub>O was detected.





| Air exposure time | ${ m Nb_2O_5/Nb}$ | ${ m NbO_2/Nb}$ | $\mathrm{NbO/Nb}$ | $\mathrm{Nb_2O/Nb}$ |
|-------------------|-------------------|-----------------|-------------------|---------------------|
| 15 min            | 0.87              | 0.12            | 0.36              | 0.08                |
| 30 min            | 0.99              | 0.14            | 0.41              | 0.11                |
| 75 min            | 1.00              | 0.15            | 0.40              | 0.07                |



As the air exposure time increases: increase of  $\mathrm{Nb}_2\mathrm{O}_5$  peak, decrease of  $\mathrm{Nb}$  metal peak. Ratio of suboxide area over metal  $\mathrm{Nb}$  area remains constant.

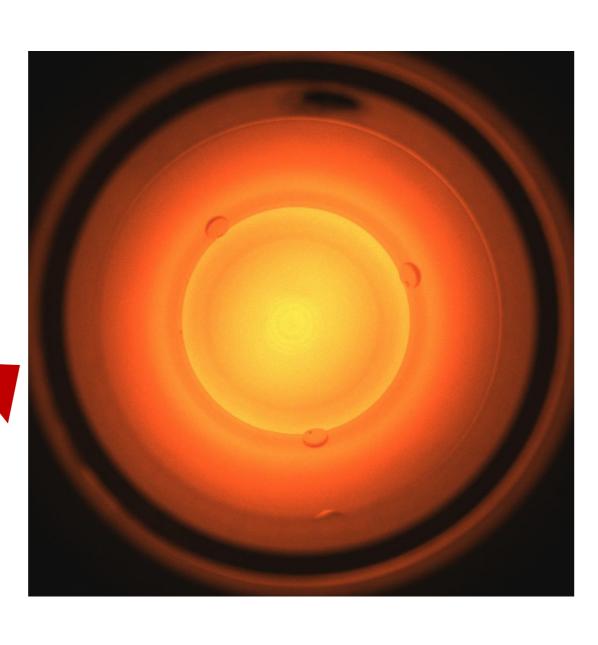
## 5. XPS analysis on plasma processed Nb samples

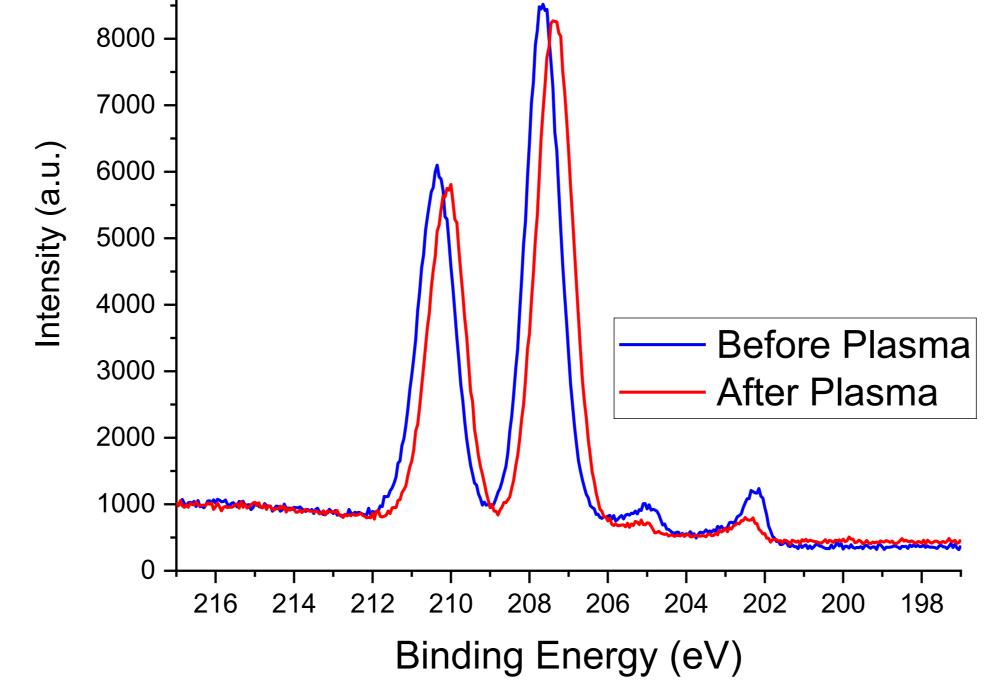
Sample preparation:

- PH 45: 800 °C x 3h + 20 μm EP
- PH 35: 2/6 N doping + 5 μm EP + 5 min HF rinse
- PH 40: 2/0 N doping + 7 μm cold EP

Samples were positioned on cavity iris and plasma processed for 6h.

- Similar results obtained on all three samples, independently of the surface treatment
- No particular change was observed in the suboxide spectra





•  $\Delta E$  between Nb and Nb<sub>2</sub>O<sub>5</sub> is decreased after plasma processing

9000 - PH 45

Relative intensity of Nb and Nb<sub>2</sub>O<sub>5</sub> is modified: ratio of Nb<sub>2</sub>O<sub>5</sub> area over Nb area consistently increases after plasma processing

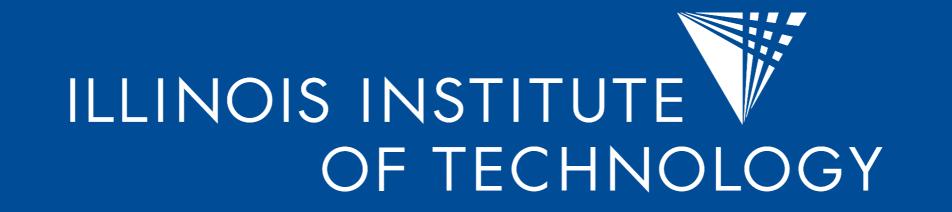
#### 6. Conclusions

- Sputtering and oxide regrowth: studied niobium oxide structure, identified multiple suboxides and extracted parameters for data analysis
- Plasma processed samples:
  - Consistent change in Nb<sub>2</sub>O<sub>5</sub>/Nb area ratio suggesting oxide thickening
  - Reduction in ΔE between Nb<sub>2</sub>O<sub>5</sub> and Nb peaks: reproducible but not fully understood yet. May be caused by oxygen vacancies in Nb<sub>2</sub>O<sub>5</sub> lattice.

No major impact on cavity performance







<sup>\* &#</sup>x27;AP': active pumping from atmosphere pressure to 10<sup>-9</sup> Torr